

Structured Electronic Design

Intrinsic CS stage:
Equivalent-input noise sources
SLiCAP model

Anton J.M. Montagne

SLiCAP MOS noise model

SLiCAP MOS noise model

LTspice symbol: SLM_noise

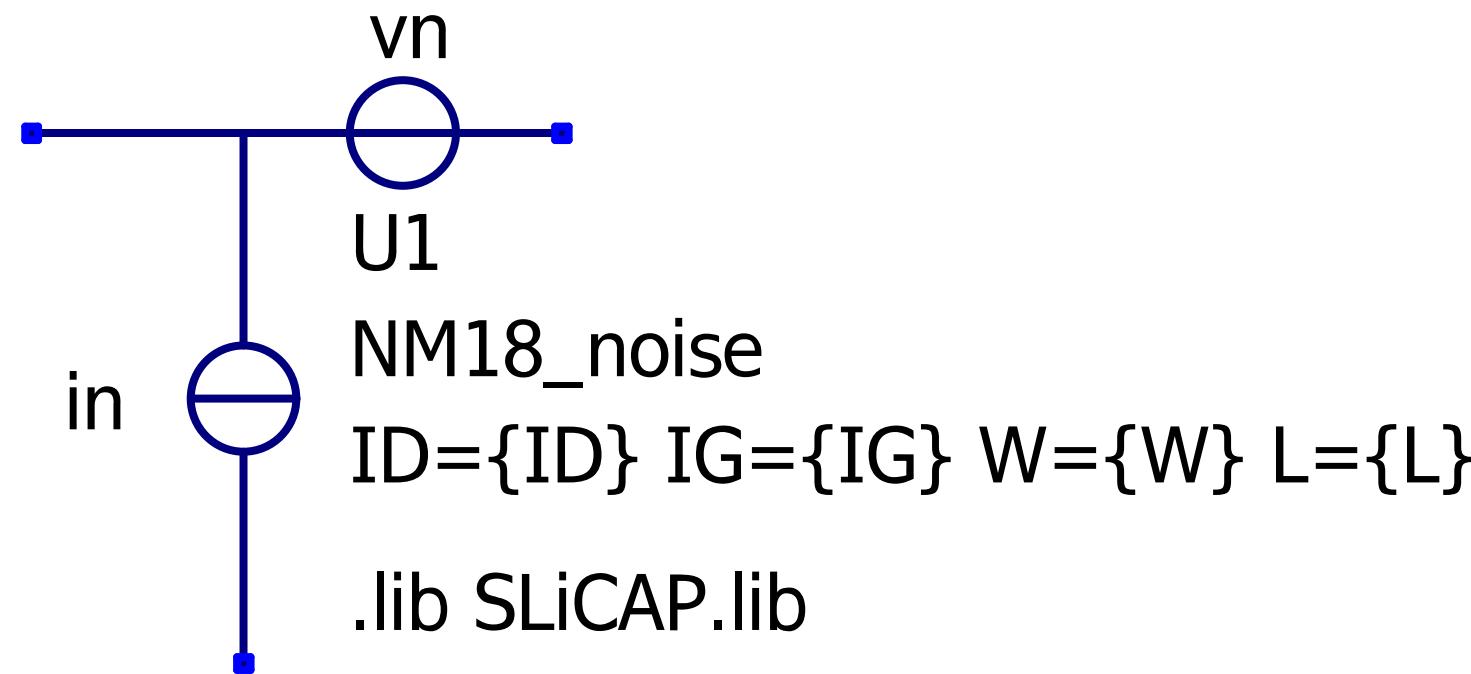
SLiCAP MOS noise model

LTspice symbol: SLM_noise

SLiCAP subcircuit NMOS18 noise model: NM18_noise

SLiCAP MOS noise model

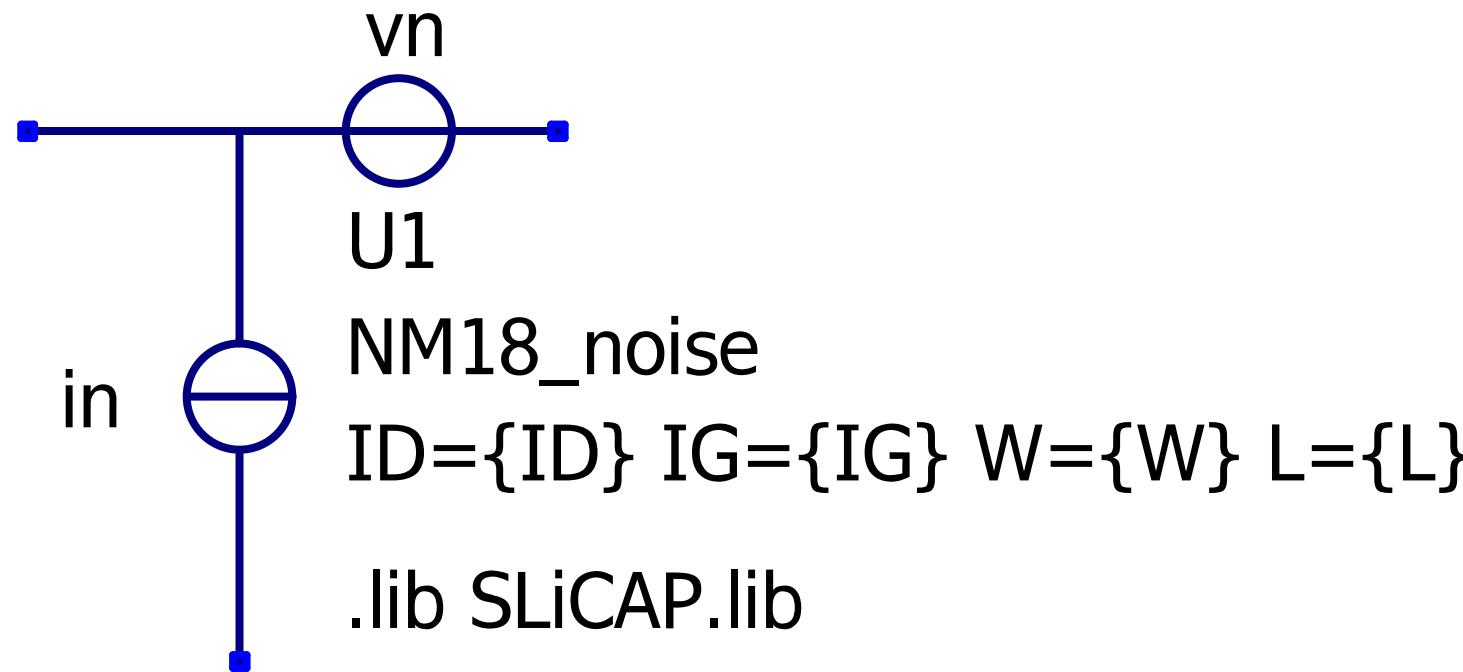
LTspice symbol: SLM_noise



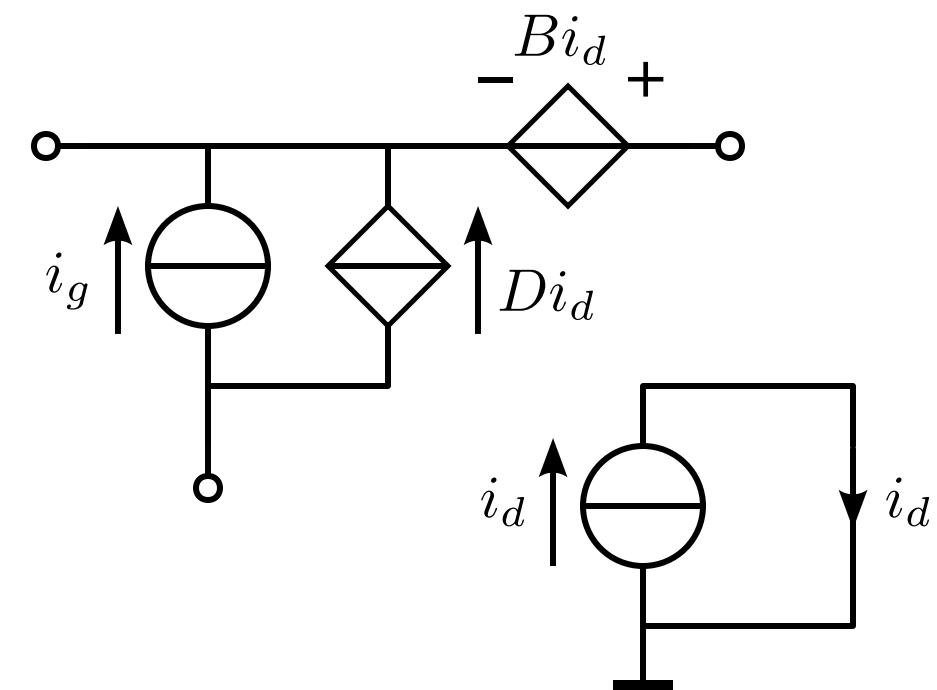
SLiCAP subcircuit NMOS18 noise model: NM18_noise

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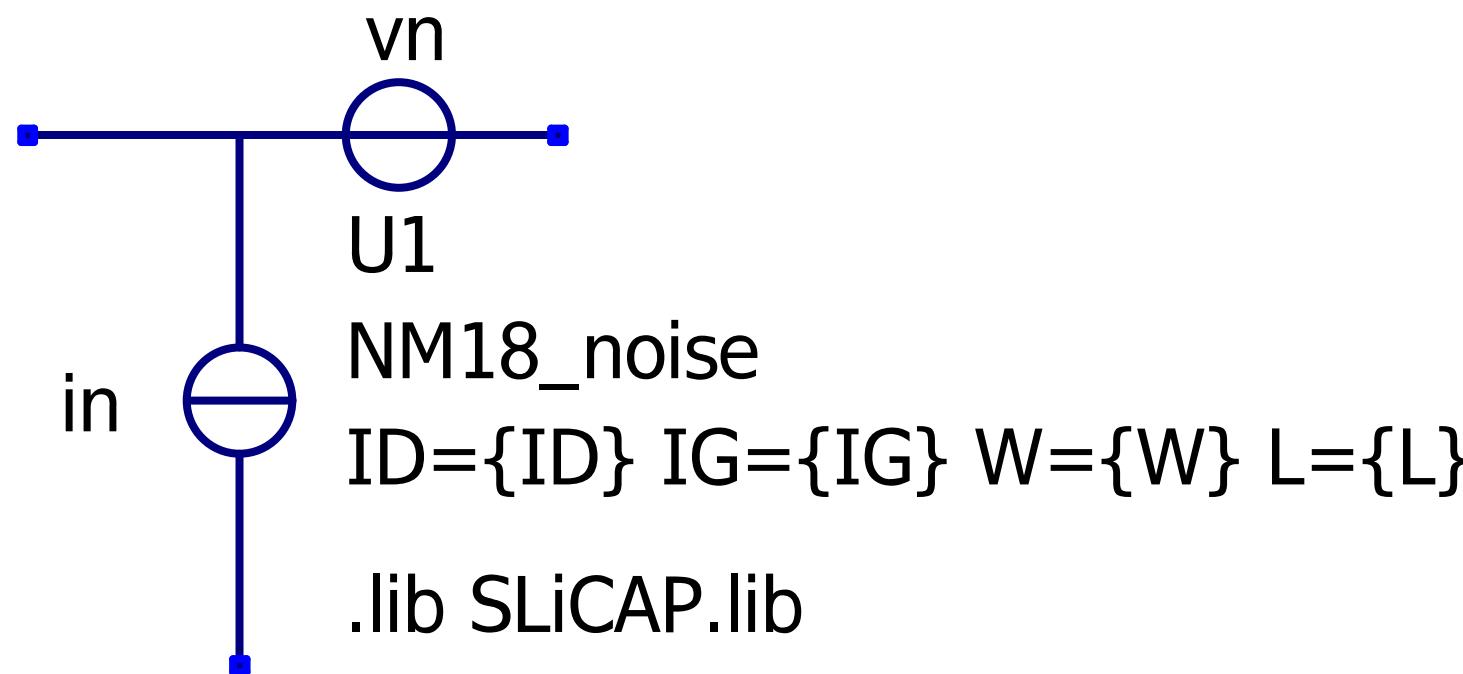


SLiCAP subcircuit NMOS18 noise model: NM18_noise



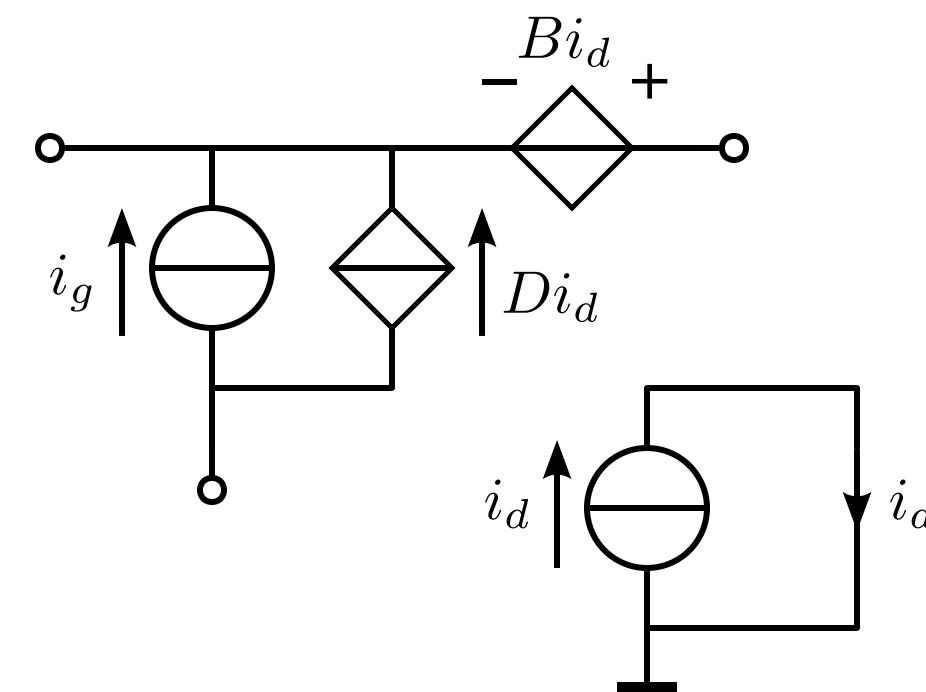
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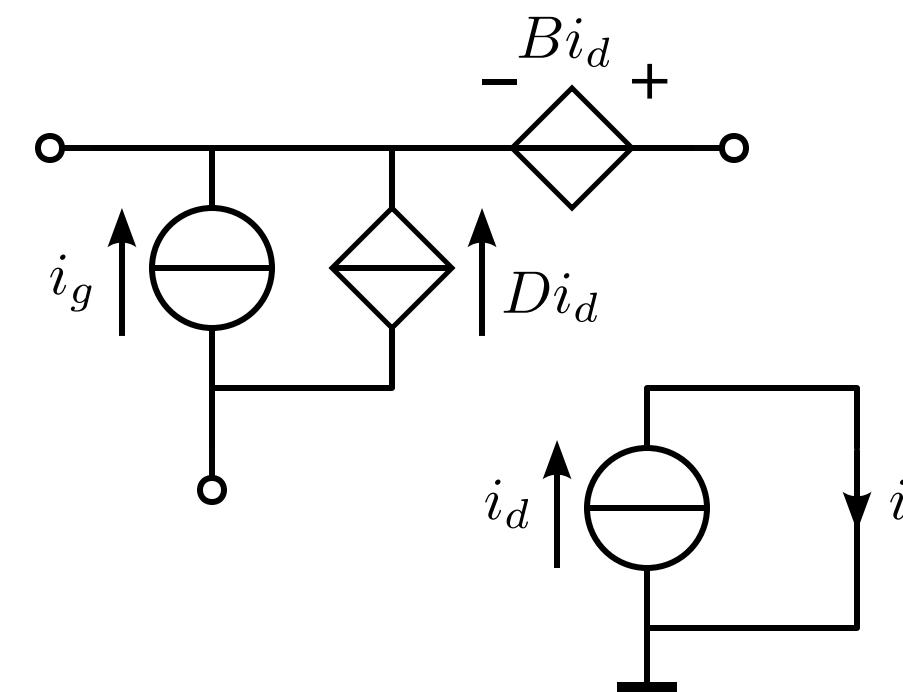
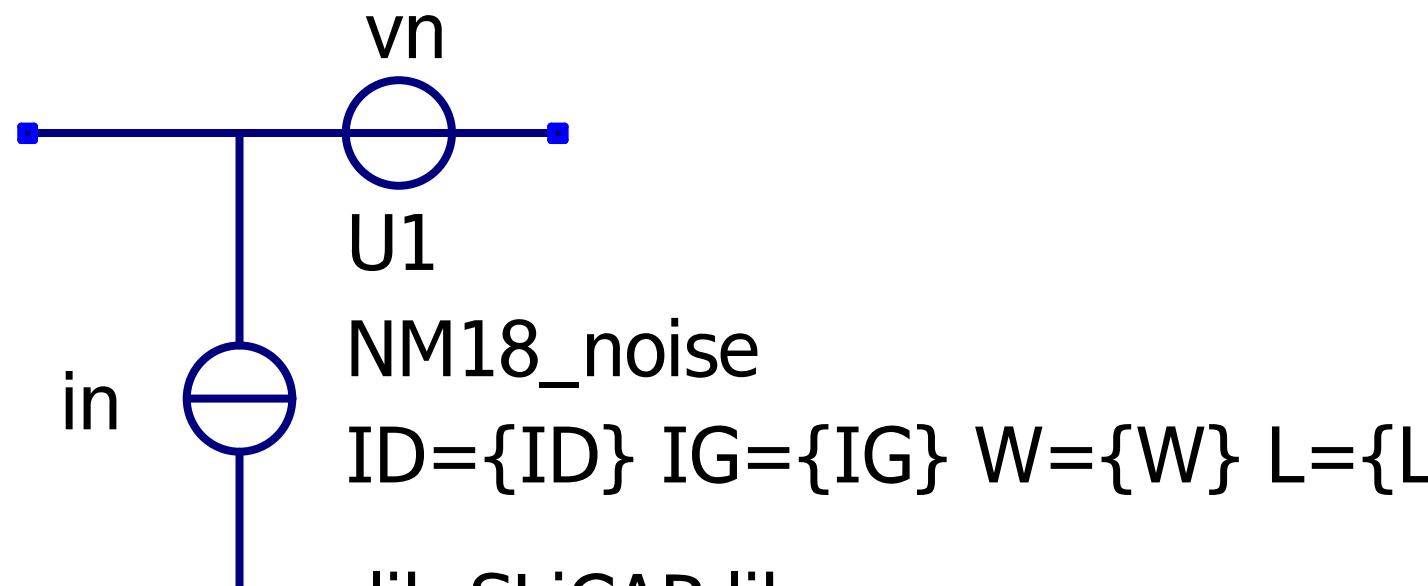
SLiCAP subcircuit NMOS18 noise model: NM18_noise

EKV model parameters saturation region



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SLiCAP subcircuit NMOS18 noise model: NM18_noise

EKV model parameters saturation region

```
.subckt NM18_noise ext comm int ID=\{ID\} IG=\{IG\} W=\{W\} L=\{L\}
* intrinsic noise sources, gate resistance should be added externally
* CMOS18 N device: copy and modify this model for other devices
I1 0 1 I value=0 noise=\{4*k*T/R_N*(1+f_ell/f)\} ; channel noise current
H1 ext int 1 10 \{1/g_m\} ; equivalent-input voltage noise
F1 ext comm 10 0 \{s/2/pi/f_T\} ; gate-induced noise
I2 ext comm I value=0 noise=\{2*q*IG\} ; gate shot noise
.param
* device equations MKV model saturated region
+ R_N = \{(1+IC)/(1/2 + 2/3*IC)/N_s_N18/g_m\}
+ IC_CRIT = \{1/((4*N_s_N18*U_T)*(Theta_N18+1/L/E_CRIT_N18))^2\}
+ g_m = \{ID/(N_s_N18*U_T*sqrt(IC*(1+IC/IC_CRIT)+0.5*sqrt(IC*(1+IC/IC_CRIT))+1))\}
+ c_gs = \{2/3*W*L*C_OX_N18 + CGSO_N18*W\}
+ c_dg = \{CGSO_N18*W\}
+ c_gb = \{CGBO_N18*2*L+(N_s_N18-1)/N_s_N18*C_OX_N18*W*L/3\}
+ c_db = \{CJB0_N18*W*LDS_N18\}
+ f_T = \{g_m/2/pi/c_iss\}
+ c_iss = \{c_gs+c_dg+c_gb\}
+ IC = \{ID*L/W/I_0_N18\}
+ f_ell = \{g_m^2*R_N*KF_N18/(4*k*T*W*L*C_OX_N18)\}
.ends
```